

Introduction to Flash Memory

Leon Romanovsky

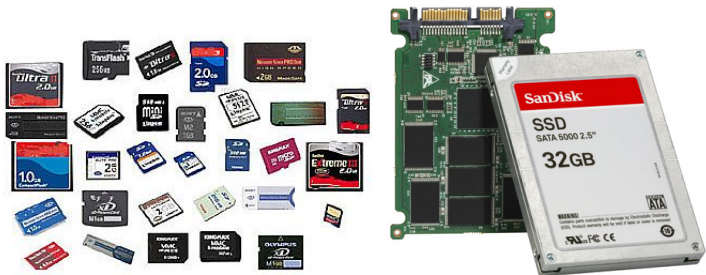
leon@leon.nu

www.leon.nu

January 13, 2013

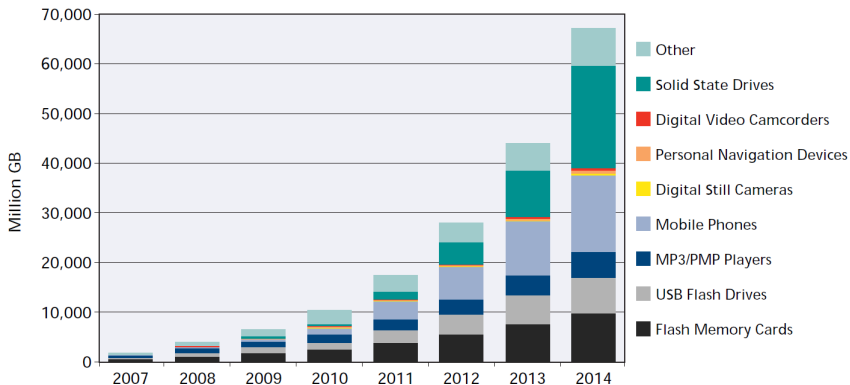
Disclaimer

Everything in this lecture shall not, under any circumstances, hold any legal liability whatsoever. Any usage of the data and information in this document shall be solely on the responsibility of the user. This lecture is not given on behalf of any company or organization.



Flash memory is a non-volatile storage device that can be electrically erased and reprogrammed.

Major Markets

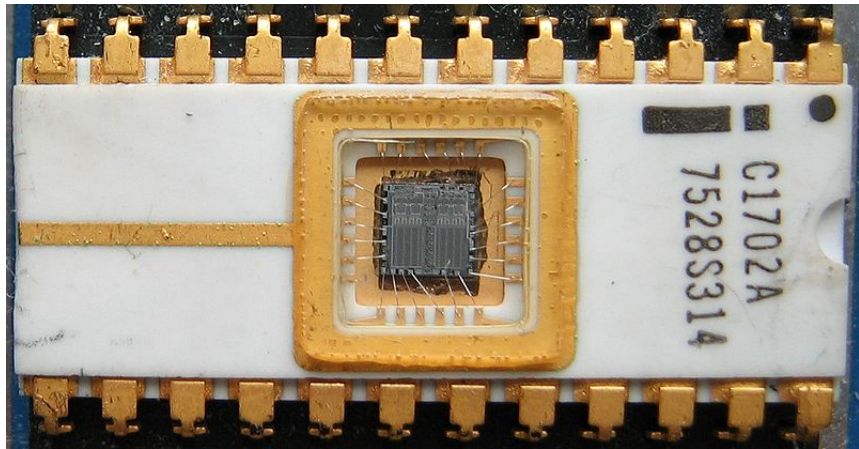


Source: Forward Insights, NAND Quarterly Insights Q3/09, www.forward-insights.com/
Report No. FI-NFL-NQ-Q309 September 2009, accessed 4/14/2010; used with permission.

Jiroft Inscription - 2600 BCE



EPR0M, Dov Frohman, Intel - 1971



First F-N Tunneling Floating gate EEPROM

United States Patent [19]
Harari

[11] 4,115,914
[45] Sep. 26, 1978

[54] **ELECTRICALLY ERASABLE
NON-VOLATILE SEMICONDUCTOR
MEMORY**

[75] Inventor: **Eliyahou Harari**, Irvine, Calif.

[73] Assignee: **Hughes Aircraft Company**, Culver
City, Calif.

[21] Appl. No.: **770,346**

[22] Filed: **Feb. 22, 1977**

Related U.S. Application Data

[62] Division of Ser. No. 671,183, Mar. 26, 1976.

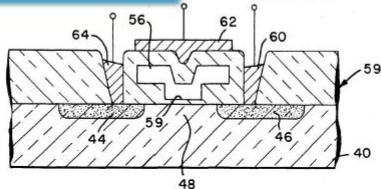
conductor Memoris" Section 4, 1972 Wescon Techni-
cal Papers.
Revs. "Silicon on Sapphire" Electronics Product
Magazine (1/1977) pp. 83-84.

Primary Examiner: **Richard W. Harp**
Assistant Examiner: **John J. Harp**

A predetermined section of this insulating layer is relatively thin to permit this section of the floating gate to be relatively close to a corresponding predetermined section of the transistor, thus facilitating the transfer of charges between the transistor substrate and the gate.

to permit this section of the float-
ing gate to be relatively close to a corresponding pre-
determined section of the transistor, thus facilitating the
transfer of charges between the transistor substrate and
the gate. When charges reach the floating gate either

Erasing is achieved by removing the charges from the floating gate by reverse tunneling through the relatively thinner insulator region.



United States Patent [19]

Masuoka et al.

[11] Patent Number: **4,531,203**

[45] Date of Patent: **Jul. 23, 1985**

[54] SEMICONDUCTOR MEMORY DEVICE AND METHOD FOR MANUFACTURING THE SAME

[75] Inventors: Fujio Masuoka; Hisakazu Izuka, both of Yokohama, Japan

[73] Assignee: Tokyo Shibaura Denki Kabushiki Kaisha, Kawasaki, Japan

[21] Appl. No.: 320,936

[22] Filed: Nov. 13, 1981

[30] Foreign Application Priority Data

Dec. 20, 1980 [JP] Japan 55/180941

Dec. 20, 1980 [JP] Japan 55/180952

[51] Int. Cl.³ G11C 11/40

[52] U.S. Cl. 365/218; 365/185

[58] Field of Search 365/185, 218

[56] References Cited

U.S. PATENT DOCUMENTS

4,203,158 5/1980 Frohman-Benschkowsky et al. 365/185

OTHER PUBLICATIONS

1980 IEEE International Solid-State Circuit Conference 152, (Feb. 1980), A 16 Kb Electrically Erasable Nonvolatile Memory.

Kupec et al., Triple Level Poly-Silicon E²Prom with Single Transistor Per Bit, 1980, IEEE.

Primary Examiner—Terrell W. Fears
Attorney, Agent, or Firm—Finnegan, Henderson, Farabow, Garrett & Dunner

[57] ABSTRACT

An erase gate is formed for erasing data from a floating gate in a semiconductor memory device having the floating gate and a control gate.

Furthermore, in order to achieve electrical insulation between the erase gate and the control gate, an insulating film formed between the erase gate and the control gate is made thicker than an insulating film formed between the floating gate and the erase gate.

4 Claims, 58 Drawing Figures

SanDisk's System-Flash Solution (1988)

Goals: Data Store, ~1M W/E, Low cost

Radical new Flash- chip architecture:

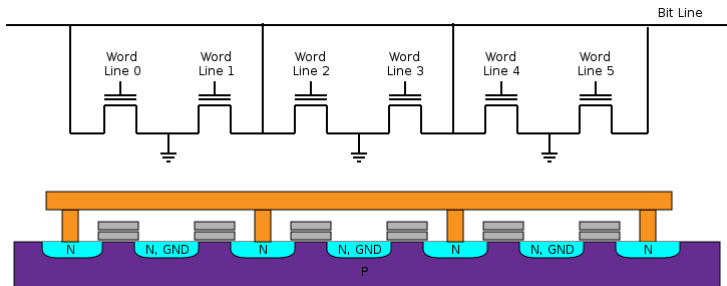
- Emulate HDD (Sector/header)
- Parallel page write, multi sector erase, serial read
- Stepped Vpg/Ver, bit by bit inhibit, prog. ref. cells
- MLC

Close-Loop Intelligent Hardware Controller:

- Manage HDD files
- Host Independent, Standard mass storage I/O
- Dynamically manage defective bits/sectors (ECC, retry, recovery, substitution, links)
- Wear-out leveling, hot count
- Adaptive W/E voltages

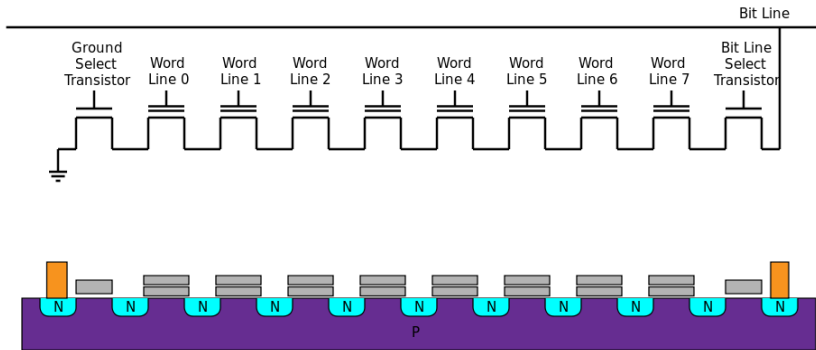
NOR Flash

- Random, direct access interface.
- Fast random reads.
- Slow erase/writes.



NAND Flash

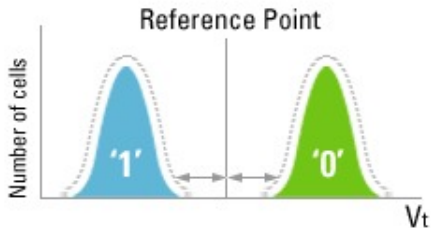
- Higher density, lower cost.
- Fast erase/write.
- Block input/output access.



Single, Multi, and 3-bit Level Flash Cells

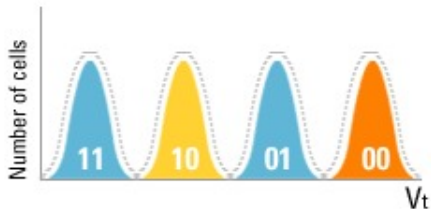
SLC

One bit per cell



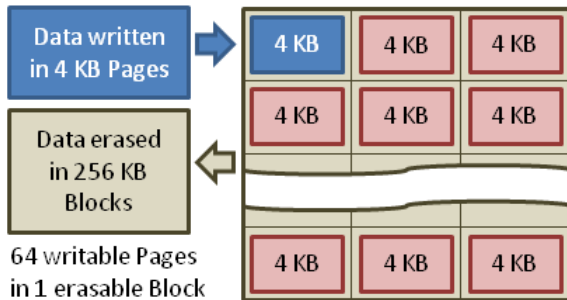
MLC

Two bits per cell



Block Level Access

- Minimal working unit, depends on size/technology.
- No read/write operation simultaneously.
- Erasing a block sets all bits to 1.
- Programming changes bits from 1 to 0.



Typical NAND Flash Pages and Blocks

Data Retention

Finite number of P/E cycles.

- Wear leveling.
- Bad block management.

□ Wear Leveling by Memory Controller IC (Conceptual Drawing)



«Program»



Occurrence of defective block



Concentration of programming in a specific block degrades memory cells and renders the block defective.



«Program»



Wear leveling



«Program»



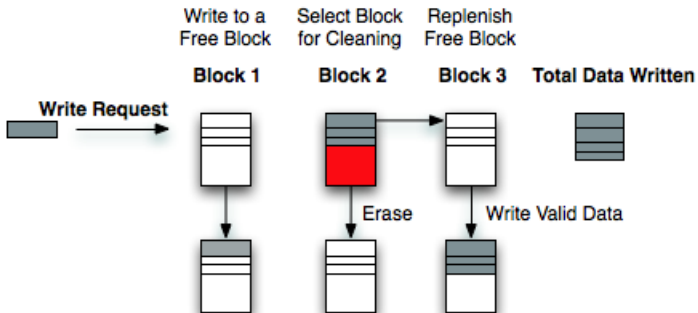
Wear leveling



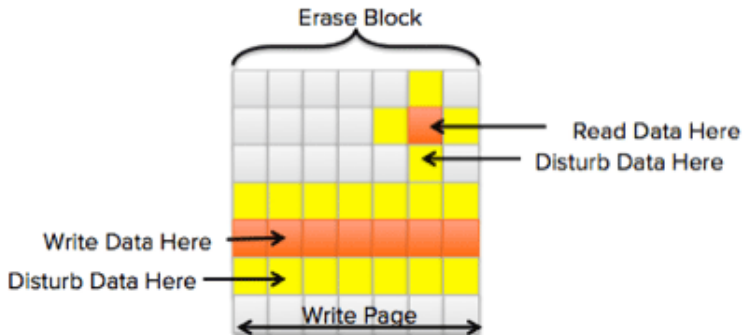
The special controller IC algorithm distributes data to avoid concentrations of programming in specific blocks.

Write Amplification

write amplification factor = $\frac{\text{data that controller has to write}}{\text{data that host wants to write}}$



Write and Read Disturb



- block-level access
- wear leveling
- read disturb
- bad blocks management
- garbage collection
- different physics
- different interfaces

- <http://persianwondersvideo.blogspot.co.il/2007/02/jiroft.html>
- <http://en.wikipedia.org/wiki/Eprom>
- http://en.wikipedia.org/wiki/Flash_memory
- <http://www.monolithic3d.com/2/post/2011/11/what-can-we-learn-from-the-success-of-eli-harari-and-s.html>